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APPLICATION NO.	PPLICATION NO. FILING DATE		FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO	
09/842,203	- 0	04/26/2001	Maurits van der Schaar	P 280250 P-0181.010-US	5405	
909	7590	12/19/2002				
		HROP, LLP	EXAMINER			
P.O. BOX 1 MCLEAN,		!		ESPLIN, DAVID B		
•				ART UNIT	PAPER NUMBER	
				2851		
				DATE MAN DE LANGUE		

DATE MAILED: 12/19/2002

Please find below and/or attached an Office communication concerning this application or proceeding.

				<i>*</i>	
		Application No.	Applicant(s)		
		09/842,203	VAN DER SCHA	VAN DER SCHAAR ET AL.	
	Office Action Summary	Examiner	Art Unit		
		D. Ben Esplin	2851		
Period f	The MAILING DATE of this communication app or Reply	ears on the cover s	heet with the correspondence a	idress	
THE - Exte after - If the - If NO - Fails - Any	ORTENED STATUTORY PERIOD FOR REPLY MAILING DATE OF THIS COMMUNICATION. Pensions of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. Pe period for reply specified above is less than thirty (30) days, a reply period for reply is specified above, the maximum statutory period were to reply within the set or extended period for reply will, by statute, reply received by the Office later than three months after the mailing ed patent term adjustment. See 37 CFR 1.704(b).	36(a). In no event, however within the statutory minimu vill apply and will expire SIX cause the application to be	r, may a reply be timely filed Im of thirty (30) days will be considered time (6) MONTHS from the mailing date of this of the come ABANDONED (35 U.S.C. & 133)	ily. communication.	
1)	Responsive to communication(s) filed on				
2a)□		— · is action is non-fina	1		
3)	Since this application is in condition for allowa			ne merits is	
,—	closed in accordance with the practice under I	Ex parte Quayle, 19	935 C.D. 11, 453 O.G. 213.	io mente io	
· _	ion of Claims Claim(s) 1 13 is/are pending in the application				
4)🖂	Claim(s) <u>1-13</u> is/are pending in the application 4a) Of the above claim(s) is/are withdraw		on.		
5)□	Claim(s) is/are allowed.	VII IIOIII COIISIGEIAU	Jii.		
	Claim(s) 1.2 and 10-13 is/are rejected.				
	Claim(s) 3-9 is/are objected to.				
· —	Claim(s) are subject to restriction and/or	election requireme	ent.		
	ion Papers	' -			
9)[The specification is objected to by the Examiner	•			
10)	The drawing(s) filed on is/are: a)□ accep	ted or b) Objected	to by the Examiner.		
	Applicant may not request that any objection to the	e drawing(s) be held i	n abeyance. See 37 CFR 1.85(a).		
11)	The proposed drawing correction filed on		b) disapproved by the Examin	er.	
. —	If approved, corrected drawings are required in rep	•	1.		
•	The oath or declaration is objected to by the Exa	aminer.			
Priority (under 35 U.S.C. §§ 119 and 120				
	Acknowledgment is made of a claim for foreign	priority under 35 U	.S.C. § 119(a)-(d) or (f).		
a)	☑ All b)☐ Some * c)☐ None of:				
	1. Certified copies of the priority documents				
	2. Certified copies of the priority documents	have been receive	ed in Application No		
* 5	3. Copies of the certified copies of the priori application from the International Bur See the attached detailed Office action for a list of	eau (PCT Rule 17.	2(a)).	Stage	
	acknowledgment is made of a claim for domestic	•		l application).	
а) The translation of the foreign language prov Acknowledgment is made of a claim for domestic	visional application	has been received.	., ,	
Attachmen					
2) 🔲 Notic	e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) nation Disclosure Statement(s) (PTO-1449) Paper No(s)	5) 🔲 No	erview Summary (PTO-413) Paper No tice of Informal Patent Application (PT ner:		

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DETAILED ACTION

Election/Restrictions

Claims 14-17 are withdrawn from further consideration pursuant to 37 CFR 1.142(b), as being drawn to a nonelected invention, there being no allowable generic or linking claim.

Applicant timely traversed the restriction (election) requirement in Paper No. 7.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 1, 2, and 10-13 are rejected under 35 U.S.C. 102(b) as being anticipated by U.S. Patent No. 4,862,008 to Oshida et al.

FIG. 4A shows a lithographic projection apparatus including a radiation system (exposure light source 4), a beam patterning structure, or mask (reticle 1), supported by a support structure, or mask stage (reticle stage)(col. 14 lines 36-40), a substrate (wafer 2) arranged on a substrate table (wafer stage)(col. 14 lines 36-42), a projection system (reduction lens 3), and an alignment system including an excitation source for producing electromagnetic radiation (reference light 501') to a surface of the substrate to induce a wave in a region of a buried substrate alignment mark (see FIG. 14A and col. 11 lines 34+), and a measurement system to direct a measurement beam (reflected laser light 514). As can be seen in the drawings, the radiation from the

excitation source is shaped so as to allow the radiation to be incident on the substrate at a plurality of angles and the measurement system detects the radiation coming off of the substrate in order to generate thickness data relating to the thickness of a layer of photoresist covering the alignment mark (col. 9 lines 35+).

Allowable Subject Matter

Claims 3-9 are objected to as being dependent upon a rejected base claim, but would be allowable if rewritten in independent form including all of the limitations of the base claim and any intervening claims.

The following is an examiner's statement of reasons for allowance:

A lithographic projection apparatus including an excitation source arranged to induce an acoustic wave in a covering layer of an alignment mark, or an excitation source arranged to induce a thermal wave in a covering layer of an alignment mark, along with the rest of the structure and function found in these claims, is not taught in the prior art.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

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U.S. Patent No. 5,004,925 to Takahashi et al. discloses a method for detecting a buried

alignment mark using an electron beam.

U.S. Patent Application Publication US 2001/0007734 to Yoshida et al. discloses a

position detecting unit capable of detecting a partially buried alignment mark.

Any inquiry concerning this communication or earlier communications from the

examiner should be directed to D. Ben Esplin whose telephone number is (703) 305-4022. The

examiner can normally be reached on Mon.-Fri. (8am-4:30 pm).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Russell E. Adams can be reached on (703) 308-2847. The fax phone numbers for the

organization where this application or proceeding is assigned are (703) 872-9318 for regular

communications and (703) 872-9319 for After Final communications.

Any inquiry of a general nature or relating to the status of this application or proceeding

should be directed to the receptionist whose telephone number is (703) 308-0956.

December 12, 2002

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